

Form PTO-1449 (modified)

List of Patents and Publications for 

## INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Atty. Docket No.

2000.108100/DE0346

Serial No.

10/624,420

Applicant

Michael Friedemann and Volker Kahlert

Filing Date:

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Group:

1753

U.S. Patent Documents

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Foreign Patent Documents

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Other Art

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## U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
SHV	A1	5,963,827	10/05/99	Enomoto <i>et al.</i>	438	629	
SHV	A2	6,306,732 B1	10/23/01	Brown	438	468	
SHV	A3	6,365,510	04/02/02	Schmidbauer <i>et al.</i>	438	675	
SHV	A4	6,380,058 B2	04/30/02	Manabe <i>et al.</i>	438	597	
	A5						

## Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
SHV	B1	WO 03/001590 A2	1/03/03	PCT	H01L	21/768	Yes
	B2						
	B3						

## Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
SHV	C1	Rossnagel <i>et al.</i> , "Thin, high atomic weight refractory film deposition for diffusion barrier, adhesion layer, and seed layer applications," <i>J. Vac. Sci. Technol.</i> , 143:1819027, 1996
SHV	C2	Zhong and Hopwood, "Ionized <sup>Plasma</sup> deposition into high aspect ratio vias and trenches," <i>J. Vac. Sci. Technol.</i> , 17:405-09, 1999
	C3	

EXAMINER:

DATE CONSIDERED:

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